

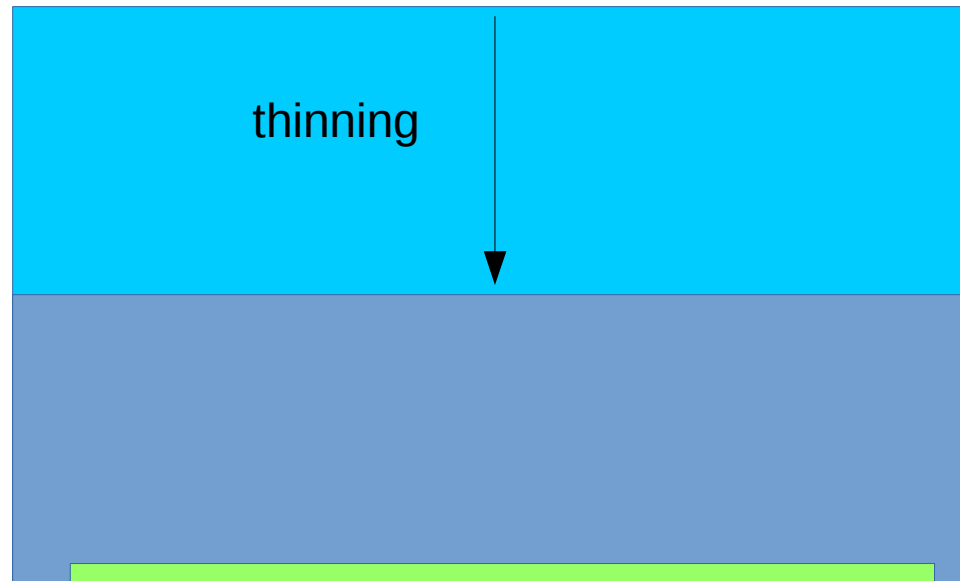


High resistivity
wafer (p)
 $\sim 1e12$

Thick enough for
backside
implantation



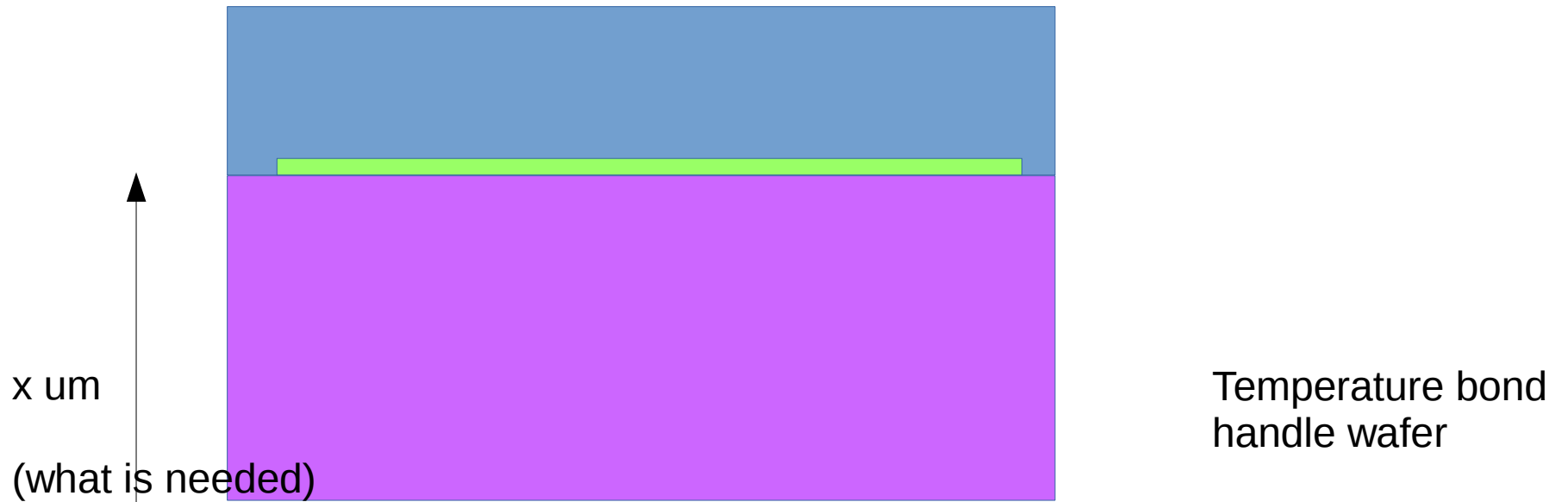
Backside
implantation
(p+)
~1e15



100 μm



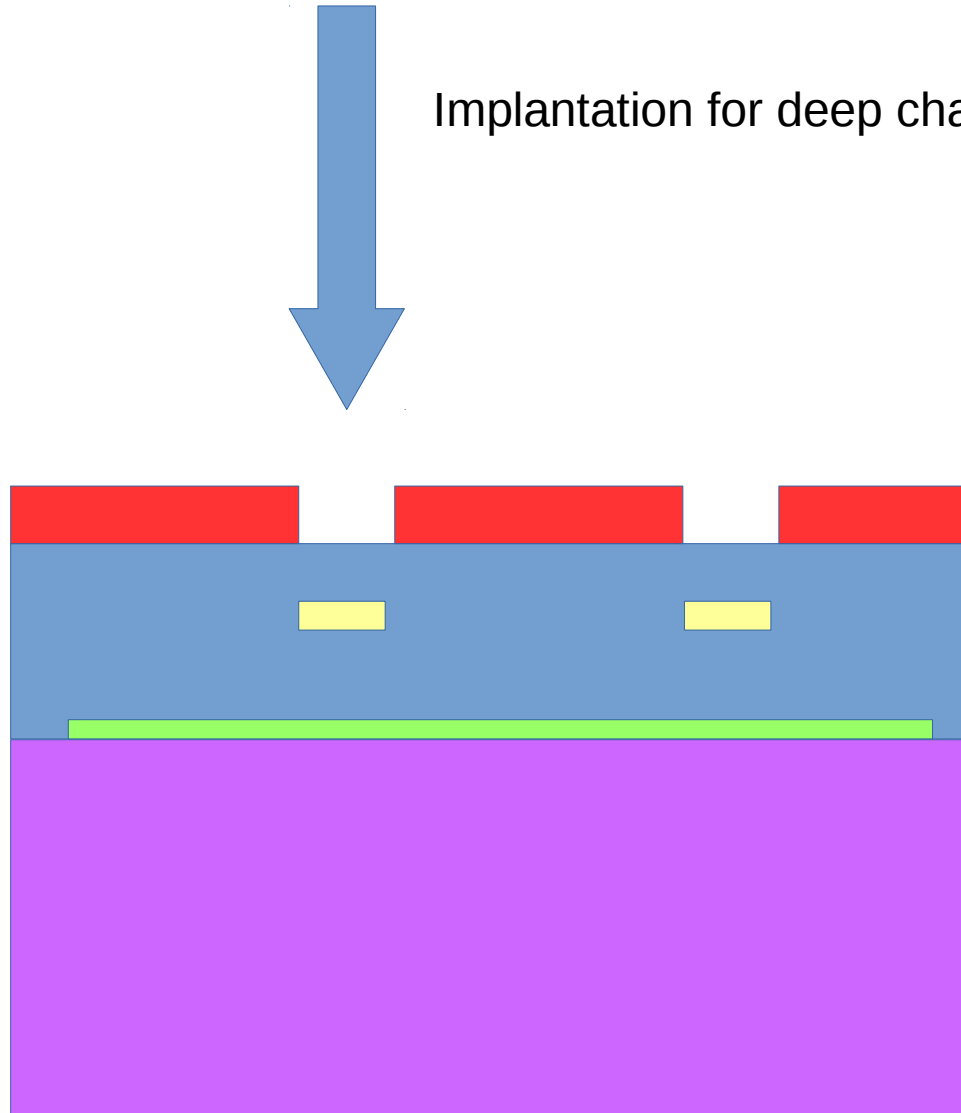
Do this before thinning?!



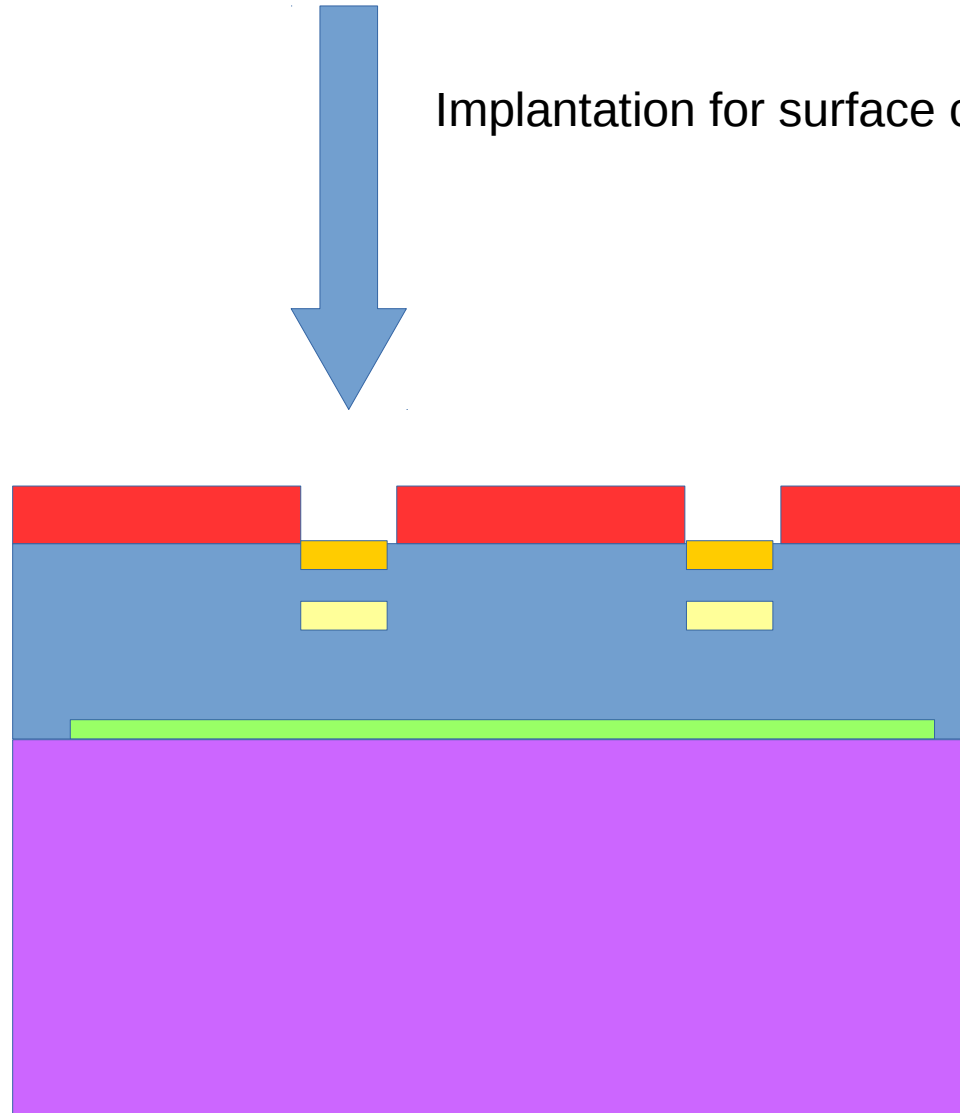


mask

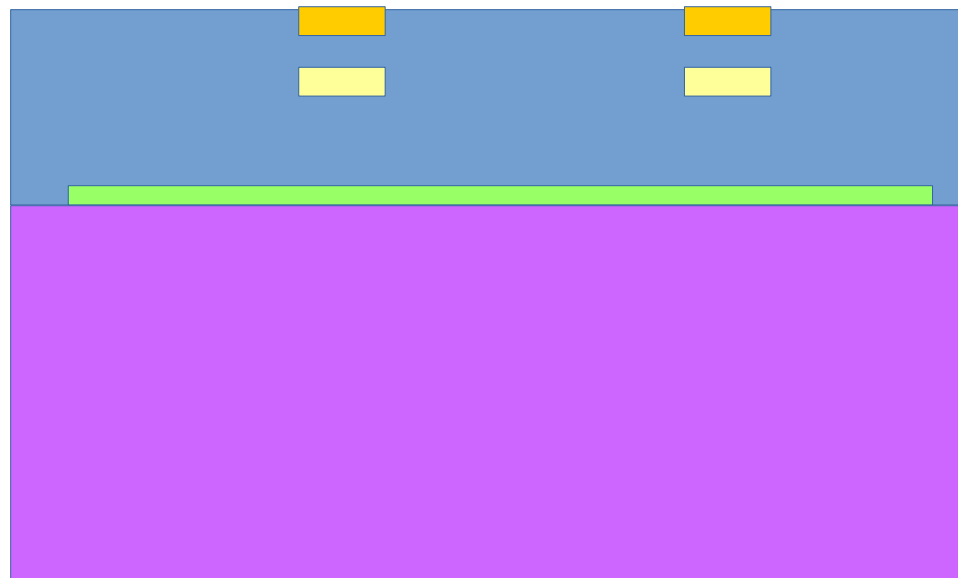
Implantation for deep charge guides (MeV)

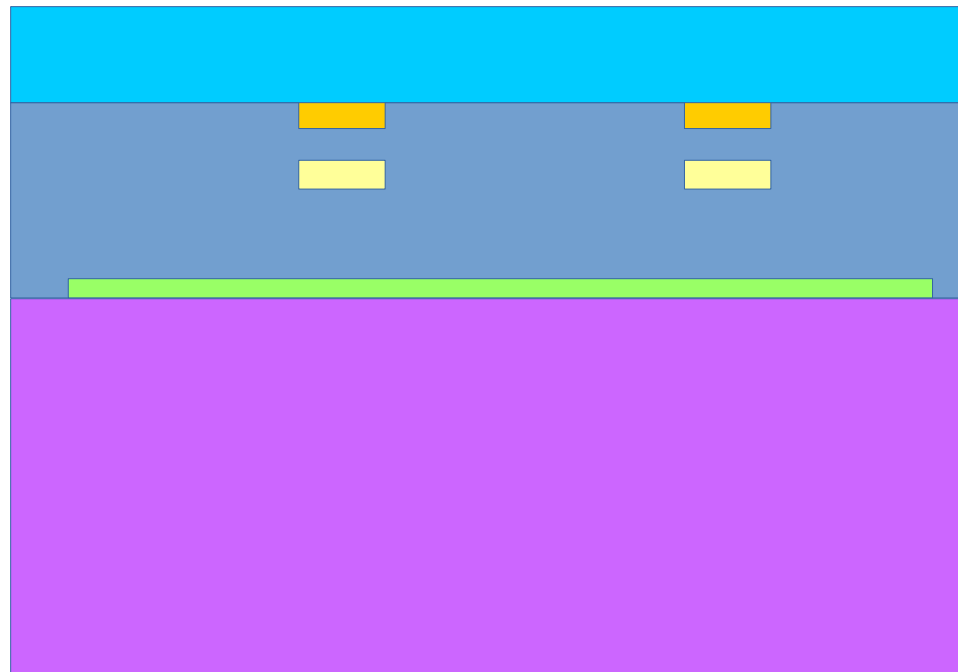


Implantation for surface charge guides (keV)

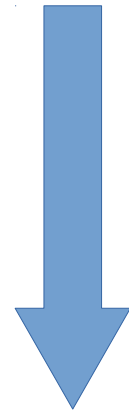


Mask removal





Epi overgrowth
(p)
 $n = \sim 1e13$ (lower
if possible)

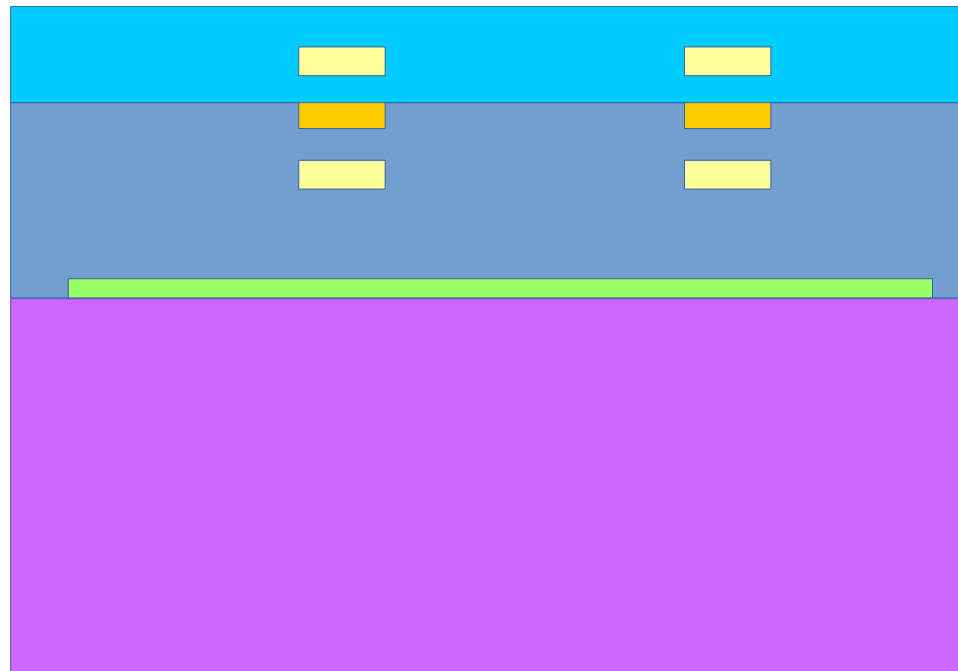


Apply mask.

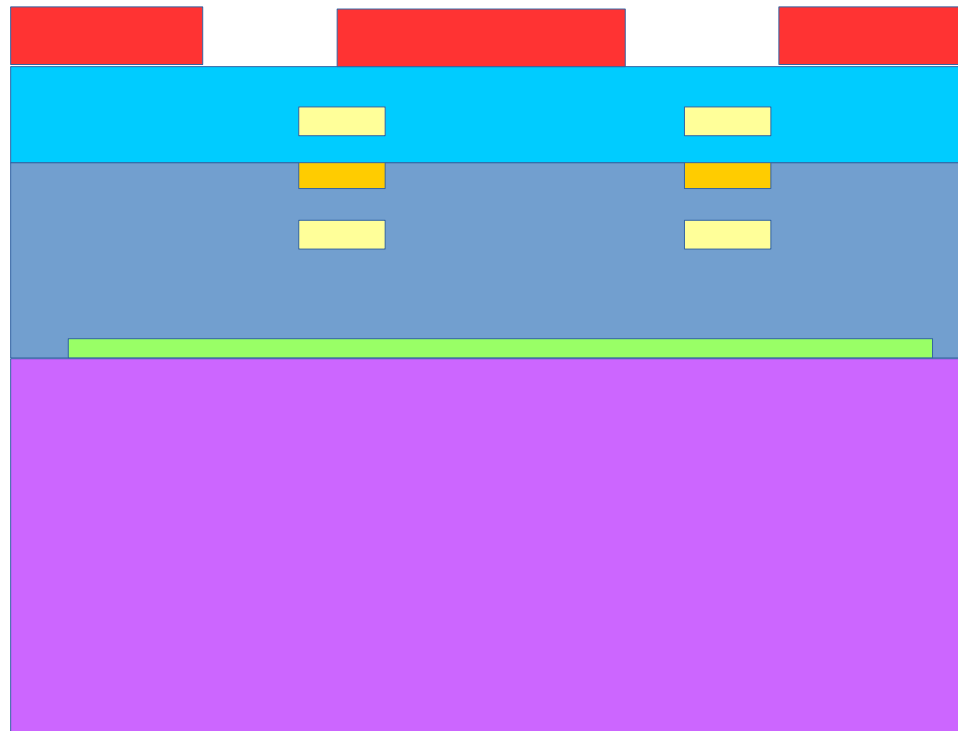
Implantation for deep charge guides (MeV)



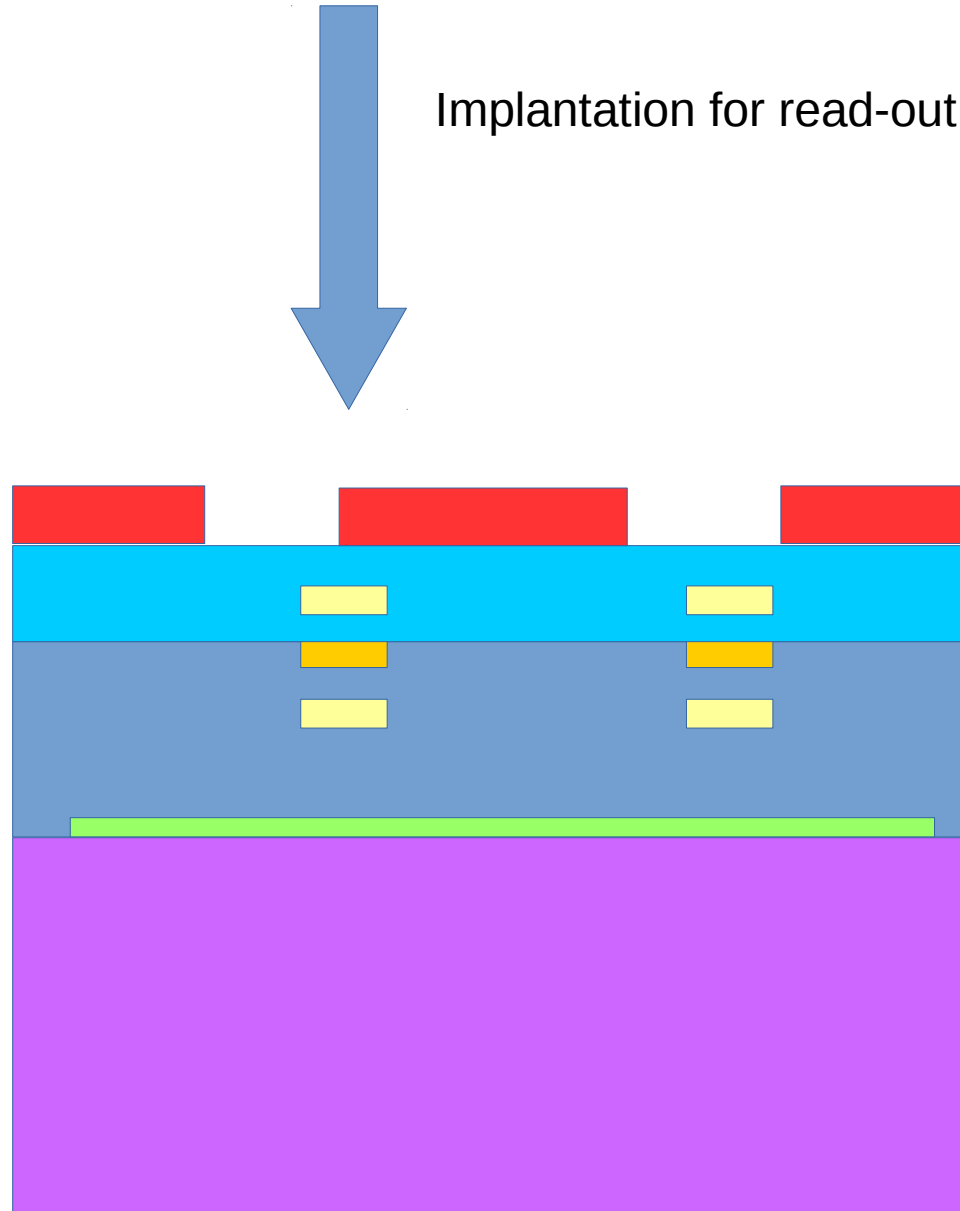
Mask removal



Mask for read-out (TimePix3); many masks



Implantation for read-out, many masks



Mask removal

